

L Number	Hits	Search Text	DB	Time stamp
1	5	((("6319821") or ("5710061") or ("6316167") or ("6153504") or ("20010045646")).PN.	USPAT; US-PGPUB	2003/06/05 13:53
4	56707	aspect adj ratio	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 13:54
10	3	((("6319821") or ("5710061") or ("6316167") or ("6153504") or ("20010045646")).PN.) and (aspect adj ratio)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 13:56
16	2	((("6319821") or ("5710061") or ("6316167") or ("6153504") or ("20010045646")).PN.) and cure\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:00
22	16062	(aspect adj ratio) with (width height size)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:01
28	3279	(aspect adj ratio) with (width with height)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:01
34	2428	(aspect adj ratio) with (width with height)	USPAT	2003/06/05 14:02
35	1563	(aspect adj ratio) near3 (width near3 height)	USPAT	2003/06/05 14:02
36	20	(aspect adj ratio) near3 (width near3 height) near3 (thickness)	USPAT	2003/06/05 14:15
37	2	("6093973").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:15
43	398263	resist photoresist photo-resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:17
49	7184	duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:16
55	1948	(resist photoresist photo-resist ) near3 (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:18
61	9	((resist photoresist photo-resist ) near3 (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) )) with (expos\$5 irradiat\$3) with (time second minute) with (known conventional\$3 typical\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:25
85	3	((resist photoresist photo-resist ) near3 (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) )) with (expos\$5 irradiat\$3 bak\$3) with (temperature) with (known conventional\$3 typical\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 15:19
91	495	(resist photoresist photo-resist ) with (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) with (heat\$3 bak\$3 temperature)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 15:23
97	110	(resist photoresist photo-resist ) with (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) with (heat\$3 bak\$3 temperature) with (cur\$3 harden\$3 insoluble)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:12

109	63	((resist photoresist photo-resist ) near3 (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))) ) same (hardmask hard-mask hard-adj-mask-etchstop-etch-stop etch adj stop) same (oxide dioxide "sio.sub.2" dielectric insulating insulator ild! imd!))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 16:13
115	1165	(hardmask hard-mask hard adj mask etchstop etch-stop etch adj stop) with ((oxide dioxide "sio.sub.2" dielectric insulating insulator ild! imd!) near2 (on over))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 16:15
121	5	((hardmask hard-mask hard adj mask etchstop etch-stop etch adj stop) with ((oxide dioxide "sio.sub.2" dielectric insulating insulator ild! imd!) near2 (on over))) same (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 16:15
127	18	(prebak\$3 pre-bak\$3 pre adj bak\$3) with ((resist photoresist photo-resist ) near3 (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:17
133	357082	(uv ultraviolet ultra-violet ultra adj violet)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:16
139	160	(prebak\$3 pre-bak\$3 pre adj bak\$3) with ((uv ultraviolet ultra-violet ultra adj violet) ) with (resist photoresist photo-resist )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:18
145	5	(prebak\$3 pre-bak\$3 pre adj bak\$3) with ((uv ultraviolet ultra-violet ultra adj violet) ) with (resist photoresist photo-resist ) with heat\$3 with (light radiation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:22
151	15	(before near3 (expos\$3 irradiat\$5)) with ((uv ultraviolet ultra-violet ultra adj violet) ) with (resist photoresist photo-resist ) with heat\$3 with (light radiation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:20
163	4508	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) near3 (blanket)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:25
157	46	(prebak\$3 pre-bak\$3 pre adj bak\$3) with (resist photoresist photo-resist ) with heat\$3 with (light radiation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:23
169	65	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) with (blanket near2 (expos\$3 irradiat\$5)) with (resist photoresist photo-resist )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:31
175	111	((prebak\$3 pre-bak\$3 pre adj bak\$3) with (resist photoresist photo-resist ) with heat\$3 with (light radiation)) ((prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) with (blanket near2 (expos\$3 irradiat\$5)) with (resist photoresist photo-resist ))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:30
181	3	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) with (blanket near2 (expos\$3 irradiat\$5)) with (resist photoresist photo-resist ) with (during "same time")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:38
187	3	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) with (flood near2 (expos\$3 irradiat\$5)) with (resist photoresist photo-resist ) with (during "same time")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:37
193	2543	((blanket flood) near2 (expos\$3 irradiat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:38

199	406	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) with (((blanket flood) near2 (expos\$3 irradiat\$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 17:41
205	22	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) with (((blanket flood) near2 (expos\$3 irradiat\$5))) with (((uv ultraviolet ultra-violet ultra adj violet) ) (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) ) with (resist photoresist photo-resist )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 18:14
211	115	etch\$4 with fluorocarbon with polymer\$3 with (oxide dielectric insulating insulator)	USPAT; US-PGPUB	2003/06/05 18:20
214	0	(etch\$4 with fluorocarbon with polymer\$3 with (oxide dielectric insulating insulator)) with (remov\$3) with ((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) ((uv ultraviolet ultra-violet ultra adj violet) ))	USPAT; US-PGPUB	2003/06/05 18:17
217	13	(etch\$4 with fluorocarbon with polymer\$3 with (oxide dielectric insulating insulator)) with (remov\$3)	USPAT; US-PGPUB	2003/06/05 18:17
223	7	fluorocarbon with polymer\$3 with (reduc\$3 decreas\$3 less smaller) with ((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) ((uv ultraviolet ultra-violet ultra adj violet) ))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:25
230	50	fluorocarbon with polymer\$3 with (reduc\$3 decreas\$3 less smaller) with (light radiation irradiat\$5 expos\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:27
237	2	fluorocarbon with polymer\$3 with (reduc\$3 decreas\$3 less smaller) with (light radiation irradiat\$5 expos\$5) with etch\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:35
244	6	fluorocarbon with polymer\$3 with (reduc\$3 decreas\$3 less smaller) with (light radiation irradiat\$5 expos\$5) with plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:36
251	5	fluorocarbon with polymer\$3 with (reduc\$3 decreas\$3 less smaller) with (light radiation irradiat\$5 expos\$5) with deposit\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:39
258	8	(fluorocarbon with polymer\$3 with (reduc\$3 decreas\$3 less smaller) with (light radiation irradiat\$5 expos\$5) with plasma) (fluorocarbon with polymer\$3 with (reduc\$3 decreas\$3 less smaller) with (light radiation irradiat\$5 expos\$5) with deposit\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:43
265	239	((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) ((uv ultraviolet ultra-violet ultra adj violet) )) near3 cur\$3) with temperature with (time seconds! minute)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:50
272	10	((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) ((uv ultraviolet ultra-violet ultra adj violet) )) near3 cur\$3) with temperature with (time seconds! minute)) with (resist photoresist photo-resist )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/05 18:47
279	141	((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) ((uv ultraviolet ultra-violet ultra adj violet) )) near3 cur\$3) with temperature with (time seconds! minute)	USPAT	2003/06/05 18:51

280	13	((((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)) ) ((uv ultraviolet ultra-violet ultra adj violet)) near3 cur\$3) with temperature with (time seconds! minute)) same (resist photoresist photo-resist )	USPAT	2003/06/05 18:51
-	194	ma-ching-tien-.in. ma-c-t.in. chen-tsung-chuan-.in. chen-t-c.in. hsu-shew-tsu-.in. hsu-s-t-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:41
-	4	ma-ching-tien-.in. chen-tsung-chuan-.in. hsu-shew-tsu-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:42
-	398263	resist photoresist photo-resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:17
-	311522	photosensitive photo-sensitive (sensitive near (photo light energy radiation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:44
-	7184	duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 14:17
-	100791	krf arf f2 "f.sub.2"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:47
-	8980	("157" "193" "248") near (nm! nanometer nano-meter nano adj meter)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:48
-	242860	(oxide dioxide) near (layer film coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:50
-	15996	etchstop etch-stop etch adj stop hardmask hard-mask hard adj mask	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:50
-	1556036	si silicon si-contain\$3 silicon-contain\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:50
-	201724	(silicon adj (nitride oxynitride oxy-nitride oxy adj nitride carbide)) "si.sub.3 n.sub.4" sion sic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:58
-	1179	((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) near (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 11:58
-	16	((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) near (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)))) same ((oxide dioxide) near (layer film coating)) same (etchstop etch-stop etch adj stop hardmask hard-mask hard adj mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 12:06
-	18	((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) near (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)))) with cur\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 12:10

-	19859	((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) with cur\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 12:12
-	6163	((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) with ((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))) (krf arf f2 "f.sub.2") ("157" "193" "248") near (nm! nanometer nano-meter nano adj meter)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 12:12
-	6524	(etchstop etch-stop etch adj stop hardmask hard-mask hard adj mask) with ((si silicon si-contain\$3 silicon-contain\$3) ((silicon adj (nitride oxynitride oxy-nitride oxy adj nitride carbide)) "si.sub.3 n.sub.4" sion sic))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 12:12
-	21	((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) with cur\$3) and (((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) with ((duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))) (krf arf f2 "f.sub.2") ("157" "193" "248") near (nm! nanometer nano-meter nano adj meter)))) and ((etchstop etch-stop etch adj stop hardmask hard-mask hard adj mask) with ((si silicon si-contain\$3 silicon-contain\$3) ((silicon adj (nitride oxynitride oxy-nitride oxy adj nitride carbide)) "si.sub.3 n.sub.4" sion sic))) and ((oxide dioxide) near (layer film coating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 12:36
-	56707	aspect adj ratio	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 12:36
-	4	((resist photoresist photo-resist ) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) near (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)))) with cur\$3 with (light radiation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/05 13:53